



(19)

(11) Publication number: **2001**

Generated Document.

PATENT ABSTRACTS OF JAPAN(21) Application number: **11241636**(51) Intl. Cl.: **B24B 37/00 B24B 37/04**(22) Application date: **27.08.99**

<p>(30) Priority:</p> <p>(43) Date of application publication: 13.03.01</p> <p>(84) Designated contracting states:</p>	<p>(71) Applicant: ASAHI CHEM IND CO L</p> <p>(72) Inventor: KOIKE HISAO IMAUCHI TOSHIO</p> <p>(74) Representative:</p>
---	---

(54) POLISHING PAD WITH POROUS RESIN WINDOW

(57) Abstract:

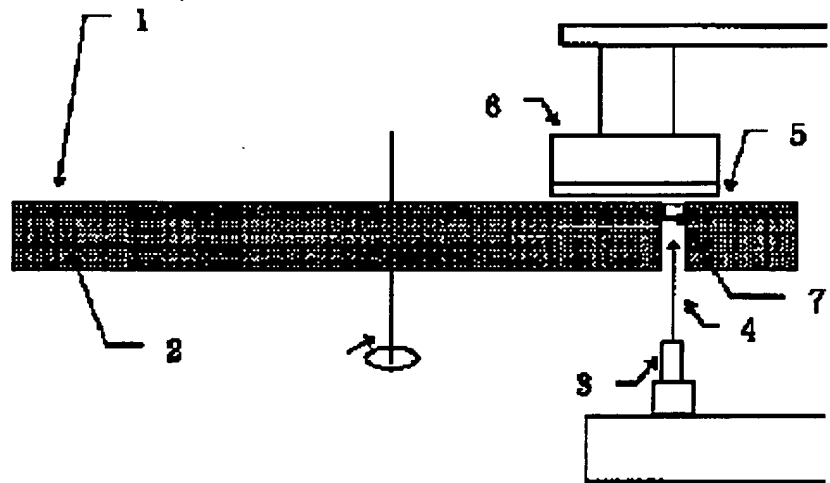
PROBLEM TO BE SOLVED: To improve the uniformity in polishing and prevent the generation of scratch by using a polishing pad for chemical mechanical polishing having a polishing region and a light transmitting region formed by a transparent porous sheet.

SOLUTION: This polishing pad 1 is formed by a transparent porous resin sheet 7 having a light transmitting region and a polishing region. A material of the transparent resin sheet 7 is a porous member having open cells and closed cells, and mainly composed of olefin resin, fluorine resin or the like, and the liquid is held in cells of the porous sheet. In a chemical mechanical polishing device, the sheet 7 is set on a position relative to a hole of a surface plate, so that a wafer 5 can be observed during the polishing. A laser interferometer 3 is placed under a window of the

transparent

surface plate, so that the laser beam 4 is collided with a surface of a wafer 5 through the sheet, and a polishing state can be analyzed. Whereby the uniformity in polishing can be improved, and the generation of scratch can be prevented.

COPYRIGHT: (C)2001,JPO



BEST AVAILABLE COPY